

IN THE SPECIFICATION

Please amend the paragraph beginning at page 24, line 27 and ending at page 26, line 1, as follows.

--In Example 1, the ink jet head was manufactured by a method for manufacturing an ink jet head shown by Figs. 1 to 7. First, the silicon substrate 1 in which the energy generating element for discharging the ink and the silicon substrate 1 on which a driver and a logic circuit were formed was prepared. Then, the positive type resist layer 2 including the photodegradable positive type resist was formed on the substrate 1 (Fig. 1). With reference to the photodegradable positive type resist, a resist solution, in which

* ~~methacrylic acid-methyl methacrylate~~ (MMA)/methacrylic acid (MAA) copolymer,

* MMA/MAA = 90/10 (weight ratio), and

* weight average molecular weight = 170000
(conversion of polystyrene)

were dissolved in diethylene glycol dimethyl ether at a solid content concentration of 25 weight%, was applied by the spin coating method. The applied resist solution was pre-baked on a hot plate at a temperature of 100 °C for three minutes, and the pre-baking was further performed in a nitrogen-replaced oven at a temperature of 150 °C for one hour to form the positive type resist layer 2 having the film thickness of 14 μm (Fig. 1). When the carboxyl group was identified the amount of hydroxyl group derived from the carboxyl group included in methacrylic acid in the resin with IR, the carboxyl group used for the intermolecular crosslinking was not more than 20%.--

Please amend the paragraph beginning at page 29, line 18 and ending at line 25, as follows.

--The ink jet head was produced in the same manner as for Example 1 except that the resin shown below was used as the positive type resist layer 2:

* ~~methacrylic acid-methyl~~ methyl methacrylate (MMA)/methacrylic acid (MAA) copolymer,

* MMA/MAA = 90/10 (weight ratio), and

* weight average molecular weight = 72000

(conversion of polystyrene).--

Please amend the paragraph beginning at page 30, line 11 and ending at line 18, as follows.

--The ink jet head was produced in the same manner as for Example 1 except that the resin shown below was used as the positive type resist layer 2:

* ~~methacrylic acid-methyl~~ methyl methacrylate (MMA)/methacrylic acid (MAA) copolymer,

* MMA/MAA = 90/10 (weight ratio), and

* weight average molecular weight = 220000

(conversion of polystyrene).--

Please amend the paragraph beginning at page 31, line 4, and ending at line 13, as follows.

--The ink jet head was produced in the same manner as for Example 1 except that the resin shown below was used as the positive type resist layer 2 and the exposure was set at 68000 mJ/cm^2 during the patterning:

* ~~methacrylic acid-methyl~~ methyl methacrylate (MMA)/methacrylic acid (MAA) copolymer,

* MMA/MAA = 93/7 (weight ratio), and

* weight average molecular weight = 170000
(conversion of polystyrene).--

Please amend the paragraph beginning at page 31, line 26, and ending at page 32, line 8, as follows.

--The ink jet head was produced in the same manner as for Example 1 except that the resin shown below was used as the positive type resist layer 2 and the exposure was set at 42000 mJ/cm^2 during the patterning:

* ~~methacrylic acid-methyl~~ methyl methacrylate (MMA)/methacrylic acid (MAA) copolymer,

* MMA/MAA = 85/15 (weight ratio), and

* weight average molecular weight = 170000
(conversion of polystyrene).--

Please amend the paragraph beginning at page 35, line 7, and ending at line 14, as follows.

--The ink jet head was produced in the same manner as for Example 1 except that the resin having the following composition and process were used as the positive type resist layer 2[.]:

* ~~methacrylic acid methyl~~ methyl methacrylate (MMA)/methacrylic acid (MAA) copolymer (MMA/MAA = 97/3 (weight ratio), weight average molecular weight = 33000 (conversion of polystyrene))₂--

Please amend the paragraph beginning at page 37, line 19 and ending at line 26, as follows.

--The ink jet head was produced in the same manner as for Example 1 except that the resin having the following composition and process were used as the positive type resist layer 2[.]:

* ~~methacrylic acid methyl~~ methyl methacrylate (MMA)/methacrylic acid (MAA) copolymer (MMA/MAA = 97/3 (weight ratio), weight average molecular weight = 33000 (conversion of polystyrene))₂--